

ABSTRACT OF THE DISCLOSURE

EXPOSURE APPARATUS, EXPOSURE METHOD, AND METHOD FOR MANUFACTURING ARTICLE

An exposure apparatus configured to expose a pattern of a mask onto a substrate includes an illumination optical system configured to illuminate the mask, a projection optical system configured to project light from the mask onto the substrate, a rotation unit configured to rotate the mask, and a control unit configured to control the rotation unit to rotate the mask based on information regarding the projection optical system.

FIG.4